



## Supplementary Materials Synaptic Characteristics from Homogeneous Resistive Switching in Pt/Al<sub>2</sub>O<sub>3</sub>/TiN Stack

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Figure S1. Negative differential resistance behavior in forming curve of Pt/Al<sub>2</sub>O<sub>3</sub>/TiN device.



Figure S2. Transition from filamentary switching to homogeneous switching in Pt/Al<sub>2</sub>O<sub>3</sub>/TiN device.



**Figure S3.** Drift characteristics of filamentary switching with self-compliance (type 2) in middle resistance states of Pt/Al<sub>2</sub>O<sub>3</sub>/TiN device.



**Figure S4.** Nonlinearity of the potentiation and depression curves for (a) type 2 and (b) type 3. Nonlinearity is calculated by following equation.

$$NL = average \left( \left| \frac{G - G_{Linear}}{G} \right| \times 100 \right)$$



Figure S5. PPF index as a function of interval time.